

**FORM PTO-1449** U.S. Department of Commerce  
 Patent and Trademark Office

Application No.:	10/523,948
Filing Date:	February 8, 2005
First Named Inventor:	Hallahan et al.
Group:	
Examiner:	
Attorney Docket No.:	1242/57 PCT/US

## List of Documents Cited by Applicant

## U.S. PATENT DOCUMENTS

Examiner Initial	Cite No.	Document Number	Publication Date	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, where relevant passages or relevant figures appear

## FOREIGN PATENT DOCUMENTS

Examiner Initials	Cite No.	Document Number (country code, no., kind code (if known))	Publication Date	Name of Patentee or Applicant	Pages, columns, lines where relevant passages appear	T

## OTHER DOCUMENTS

Examiner Initials	Cite No.	Include Author (in CAPITAL LETTERS), Title, Journal, Date, Pertinent Pages, Etc.	T
	1	<del>International Search Report for corresponding PCT Appl. No. PCT/US03/25015 dated April 24, 2004.</del>	
	2	<del>International Preliminary Examination Report for corresponding PCT Appl. No. PCT/US03/25015 dated June 9, 2004.</del>	
SG	3	Database HCAPLUS on STN, (Columbus, OH, USA) No. 127:158517, ROSENZWEIG ET AL., "Radiosensitization of human tumor cells by the phosphatidylinositol 3-kinase inhibitors wortmannin and LY294002 correlates with inhibition of DNA-dependent protein kinase and prolonged G2-M delay", <u>Clinical Cancer Research</u> , <b>3(7)</b> : 1149-1156, 1997. ABSTRACT	
SG	4	Database EMBASE on STN, (Columbus, OH, USA), No. 2001275912, GUPTA ET AL., "The ras radiation resistance pathway", <u>Cancer Research</u> , <b>61(10)</b> : 4278-4282, May 15, 2001.	
SG	5.	Database EMBASE on STN, (Columbus, OH, USA), No. 1999054256, KRASILNIKOV ET AL., "Contribution of phosphatidylinositol 3-kinase to radiation resistance in human melanoma cells", <u>Molecular Carcinogenesis</u> , <b>24(1)</b> : 64-69, 1999.	

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/Shirley Gembeh/

DATE CONSIDERED

5/27/08

\*Examiner Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.